

Notice of References Cited

Application/Control No.

09/744,420

Applicant(s)/Patent Under
Reexamination
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Examiner

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Art Unit

1762

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-6126743	10-2000	Saegusa et al.	117/68
	C	US-6048621	04-2000	Gallego et al.	428/432
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
*	U	Dai, Buorui et al.; "A Study of Tungsten Oxide Thin Films Prepared by Plasma Enhanced CDV (PECVD)"; Adv. Sci. Technol. (1995), 5 (Advances in Inorganic Films and Coatings), pages 407-414, Changchun, P.R. of China; XP002123373.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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